## IN THE CLAIMS

Please cancel claim 2.

Please amend claims 1, 3, 5, 6, 22, 25, and 28 as follows:

1. (Currently Amended) A no-flow underfill material comprising:

an epoxy-based resin; represented by:

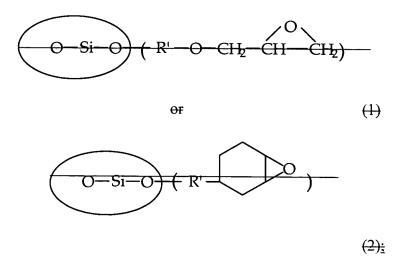
$$R1 - R3 - R2$$

where R1 includes SiO<sub>2</sub>:

R2 is a reactive organic functional group selected from the group consisting of an isocynate group and a carbonyl chloride group;

R3 is an organic chain segment;

including oxirane grafted silica particles; represented by



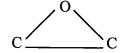
wherein R' is an organic linkage between a surface of a silica particle and a diglycidyle ether type oxirane group and not a reaction product of a reaction between an oxirane group and an hydroxyl group;

at least one agent acting as a cross-linking hardener and a curing catalyst capable of

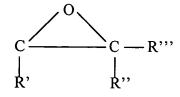
09/844,855

catalyzing the curing of the epoxy-based resin; and a fluxing agent.

- 2. (Cancelled)
- 3. (Currently Amended) The material of claim 2 1 wherein R1 is a surface-grafted fused silica particle with a size less than 50 microns.
- 4. (Previously Presented) The material of claim 3 wherein a structure of R1 is made cyclic.
- 5. (Currently Amended) The material of claim 2 1 wherein R1 includes an oxygen atom linked to the silica particle, R3 being linked to the oxygen atom.
- 6. (Currently Amended) The material of claim 2 <u>1</u> wherein R2 includes an oxirane group represented by:

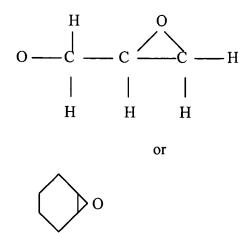


7. (Previously Presented) The material of claim 6 wherein R2 is represented by:



Wherein R', R", and R" are hydrogen or alkyl groups.

8. (Previously Presented) The material of claim 7 wherein R2 is represented by:



- 9. (Previously Presented) The material of claim 1 wherein the agent acting as a cross-linking hardener and a catalyst includes both a hardener and a catalyst.
- 10. (Previously Presented) The material of claim 1 wherein the cross-linking hardener is selected from the group consisting of an imidazole and its derivatives, an amine, a triphenylphosphine, an anhydride, a polyamide, a polyamide amine, a phenolic resin, and an onium salt.
- 11. (Previously Presented) The material of claim 1 wherein the catalyst is selected from the group consisting of an imidazole and its derivatives, an imidazolium salt, a triphenylphosphine, a tertiary amine, and an onium salt.
- 12. (Previously Presented) The material of claim 1 wherein the fluxing agent is dissolved in a mixture of the epoxy-based resin and the agent acting as a cross-linking hardener.

- 13. (Previously Presented) The material of claim 1 wherein the fluxing agent is selected from the group consisting of an organic carboxylic acid, a polymeric fluxing agent, and an organic compound that contains one or more hydroxyl groups.
- 14. (Previously Presented) The material of claim 1 further comprising: an adhesion promoter.
- 15. (Previously Presented) The material of claim 14 wherein the adhesion promoter is selected from the group consisting of a silane coupling agent, an organo-ziconate, and an organo-titanate.
- 16. (Previously Presented) The material of claim 1 further comprising: a non-iomic surfactant.
- 17. (Previously Presented) The material of claim 16 wherein the surfactant is selected from the group consisting of polyol, a siloxane compound, and a fluorinated compound.
- 18. (Previously Presented) The material of claim 1 further comprising: fused silica.
- 19. (Previously Presented) The material of claim 1 further comprising: silver flakes.

- 20. (Previously Presented) The material of claim 1 further comprising: thermally conductive particles.
- 21. (Previously Presented) The material of claim 20 wherein the thermally conductive particles include a material selected from the group consisting of silicon nitride, silicon borate, alumina, diamond, and silicon oxide.
- 22. (Currently Amended) A no-flow underfill material comprising: an epoxy resin; represented by:

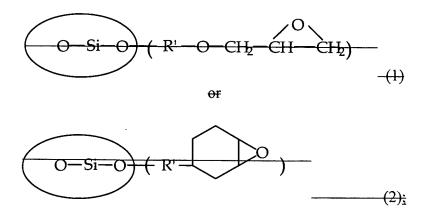
$$R1 - R3 - R2$$

where R1 includes SiO<sub>2</sub>:

R2 is a reactive organic functional group selected from the group consisting of an isocynate group and a carbonyl chloride group;

R3 is an organic chain segment;

including oxirane grafted silica particles and being represented by



wherein R' is an organic linkage between a surface of a silica particle and a diglycidyle ether type oxirane group and not a reaction product of a reaction between an oxirane group and an hydroxyl

group;

at least one agent acting as a cross-linking hardener and a curing catalyst capable of catalyzing the curing of the epoxy resin; and

a fluxing agent.

- 23. (Previously Presented) The no-flow underfill material of claim 22 further comprising:
  - an adhesion promoter;
  - a non-ionic surfactant;

fused silica;

silver flakes; and

thermally conductive particles.

- 24. (Previously Presented) The no-flow underfill material of claim 22 wherein the agent acting as a cross-linking hardener and a catalyst includes both a hardener and a catalyst.
- 25. (Currently Amended) A semiconductor package comprising:

a package substrate;

bond pads on the substrate;

a semiconductor die;

contact pads on the semiconductor die;

a respective conductive bump on each contact pad, the die being located so that each bump is in contact and attached to a respective bond pad; and

an underfill material filling regions between the bumps and including at least an epoxy-

09/844,855

based resin; represented by:

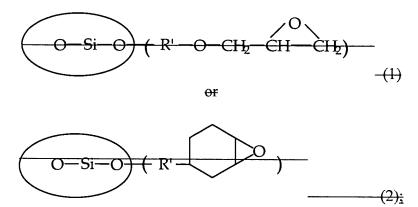
$$R1 - R3 - R2$$

where R1 includes SiO<sub>2</sub>:

R2 is a reactive organic functional group selected from the group consisting of an isocynate group and a carbonyl chloride group;

R3 is an organic chain segment;

including oxirane grafted silica particles and being represented by



wherein R' is an organic linkage between a surface of a silica particle and a diglycidyle ether type oxirane group and not a reaction product of a reaction between an oxirane group and an hydroxyl group;

at least one agent acting as a cross-linking hardener and a curing catalyst capable of catalyzing the curing of the epoxy resin; and

a fluxing agent.

- 26. (Canceled)
- 27. (Cancelled)

09/844,855

28. (Currently Amended) A semiconductor package comprising:

a package substrate;

bond pads on the substrate;

a semiconductor die;

contact pads on the semiconductor die;

a respective conductive bump on each contact pad, the die being located so that each bump is in contact and attached to a respective bond pad; and

an underfill material filling regions between the bumps and including at least an epoxy-based resin; represented by:

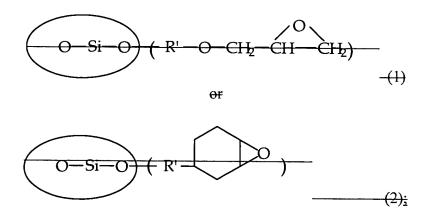
$$R1 - R3 - R2$$

where R1 includes SiO<sub>2</sub>:

R2 is a reactive organic functional group selected from the group consisting of an isocynate group and a carbonyl chloride group;

R3 is an organic chain segment;

including oxirane grafted silica particles and being represented by



wherein R' is an organic linkage between a surface of a silica particle and a diglycidyle ether type

oxirane group and not a reaction product of a reaction between an oxirane group and an hydroxyl group.

at least one agent acting as a cross-linking hardener and a curing catalyst capable of catalyzing the curing of the epoxy resin; and

a fluxing agent.

- 29. (Previously Presented) The material of claim 1, wherein R' is selected from the group consisting of a urethane group and a carboxyl group.
- 30. (Previously Presented) The no-flow material of claim 22, wherein R' is selected from the group consisting of the urethane group and the carboxyl group.
- 31. (Previously Presented) The semiconductor package of claim 25, wherein R' is selected from the group consisting of the urethane group and the carboxyl group.